## Electronic Supporting Information

## Direct Growth of Doping Controlled Monolayer $\mathrm{WSe}_{2}$ by

## Selenium-Phosphorus Substitution

Won Tae Kang ${ }^{\text {a }}$, Il Min Lee ${ }^{\text {a }}$, Seok Joon Yun ${ }^{\text {b,c }, ~ Y o u n g ~ I l ~ S o n g ~}{ }^{\text {d }}$, Kunnyun Kime ${ }^{\text {e }}$ Do-Hwan Kim ${ }^{\text {b }}$, Yong Seon Shina ${ }^{\text {a }}$, Kiyoung Lee ${ }^{f}$, Jinseong Heo ${ }^{\mathrm{f}}$, Young-Min Kim ${ }^{\text {b,c }}$, Young Hee Lee ${ }^{\text {b,c }}$ and Woo Jong Yu* ${ }^{\text {a }}$
${ }^{\text {a.Department of Electronic and Electrical Engineering, Sungkyunkwan University, Suwon, 16419, Republic }}$ of Korea.
${ }^{\text {b }}$ Department of Energy Science, Sungkyunkwan University, Suwon, 16419, Republic of Korea.
c.IBS Center for Integrated Nanostructure Physics, Institute for Basic Science (IBS), Sungkyunkwan University, Suwon, 16419, Republic of Korea.
${ }^{\text {d. Department of Advanced Materials Science \& Engineering, Sungkyunkwan University, Suwon, 16419, }}$ Republic of Korea.
e.Korea Electronics Technology Institute, Seongnam, 13509, Republic of Korea.
f.Samsung Advanced Institute of Technology, Suwon, 16678, Korea.
*Corresponding author E-mail: micco21@skku.edu


Figure S1. Schematic illustration of the domain shape changes and their comparison between intrinsic and Pdoped $\mathrm{WSe}_{2}$. Schematic ball-and-stick models for the different shapes of the monolayer $\mathrm{WSe}_{2}$ structure. The initial crystal structure on the left shows two types ( W or Se ) of $\mathrm{WSe}_{2}$ terminations. The schematic diagram on the right illustrates the domain shape changing procedure depending on the $\mathrm{W}: \operatorname{Se} \& \mathrm{P}$ rates of the two different terminations.


Figure S2. AFM images of P-doped $\mathrm{WSe}_{2}$ layers. (a) Optical image of CVD grown P-doped $\mathrm{WSe} \mathrm{e}_{2}$ layers. (b) AFM image of the dotted area in (a). Height profile of a $\mathrm{WSe}_{2}$ layer taken across the dotted line in (b), which indicates the monolayer thickness.


Figure S3. Raman and photoluminescence spectra of other intrinsic and p-doped $\mathrm{WSe}_{2}$ flakes. (a) Scanning Raman intensity at the $\mathrm{E}^{1}{ }_{2 \mathrm{~g}}$ peak of intrinsic $\mathrm{WSe}_{2}$. (b) Raman spectrum of intrinsic $\mathrm{WSe}_{2}$. (c) Scanning photoluminescence of intrinsic $\mathrm{WSe}_{2}$. (d) Photoluminescence spectrum of intrinsic $\mathrm{WSe}_{2}$. (e) Scanning Raman intensity at the $\mathrm{E}^{1}{ }_{2 \mathrm{~g}}$ peak of P-doped $\mathrm{WSe}_{2}$. (f) Raman spectrum of P-doped $\mathrm{WSe}_{2}$. (g) Scanning photoluminescence of P -doped $\mathrm{WSe}_{2}$. (h) Photoluminescence spectrum of P-doped $\mathrm{WSe}_{2}$. Scale bars are $5 \mu \mathrm{~m}$.

Supporting information 1: 2D carrier concentration calculation

The 2D carrier concentration in an p-type semiconductor is derived from the drift current density ( J$)^{1,2}$ equation:

$$
\begin{equation*}
J=q n \mu_{n} E+q p \mu_{p} E=\sigma E \tag{Equation1}
\end{equation*}
$$

Where, q is the electron charge, E is the electron field, n is electron concentration, p is hole concentration, $\mu_{\mathrm{n}}$ is electron mobility, $\mu_{\mathrm{p}}$ is hole mobility, and $\sigma$ is conductivity respectively.

P-doped $\mathrm{WSe}_{2}$ is p-type semiconductor materials with hole majority carrier (equal to 2 D carrier concentration, $n_{2 d}$, electron minority carrier can be neglected and the supplementary equation 1 becomes:

$$
J=q n_{2 d} \mu_{p} E \quad \text { (Equation 2) }
$$

Carrier concentration can be calculated by:

$$
\begin{equation*}
n_{2 d}=\frac{J}{q \mu_{p} E}=\frac{\sigma}{q \mu_{p}} \tag{Equation3}
\end{equation*}
$$

To calculate the conductivity, we use the following equation:

$$
\begin{equation*}
\sigma=\frac{I_{d s} L}{V_{d s} W} \tag{Equation4}
\end{equation*}
$$

Where, $I_{d s}$ is the drain current, $V_{d s}$ is the drain voltage, $L$, and $W$ are the channel length and channel width, respectively.

To calculate the hole mobility, we use the following equation:

$$
\begin{equation*}
\mu_{p}=\frac{G_{m} L}{C_{i} V_{d s} W} \tag{Equation5}
\end{equation*}
$$

Where, $G_{m}$ and $C_{i}$ are transconductance and capacitance per unit area, respectively.
Using above conductivity and hole mobility equation, the equation 3 becomes:

$$
\begin{equation*}
n_{2 d}=\frac{I_{d s} \quad L}{q \mu_{p} V_{d s} W}=\frac{I_{d s} C_{i}}{q G_{m}} \tag{Equation6}
\end{equation*}
$$

Based on the conductivity-voltage characteristic in Figure 7b, we extract the doping concentrations.

## References

Q. A. Vu, Y. S. Shin, Y. R. Kim, V. L. Nguyen, W. T. Kang, H. Kim, D. H. Luong, I. M. Lee, K. Lee, D. Ko, J. Heo, S. Park, Y. H. Lee, W. J. Yu, Nat. Commun., 2016, 7, 1-8.
H. Y. Jeong, Y. Jin, S. J. Yun, J. Zhao, J. Baik, D. H. Keum, H. S. Lee, Y. H. Lee, Adv. mater., 2017, 29, 1-6.

